

Attorney's Docket:
TI-36749

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Christopher L. Kelley
Filing Date: December 10, 2003
Title: TEMPERATURE CONTROL ASSEMBLY FOR USE IN
ETCHING PROCESSES AND AN ASSOCIATED
RETROFIT METHOD

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Applicant respectfully requests, pursuant to 37 C.F.R. §§1.56, 1.97, and 1.98, that the document listed on the attached PTO-1449 form be considered and cited in the examination of the above-identified application. Furthermore, pursuant to 37 C.F.R. §§1.97(g) and (h), Applicant makes no representation that this document qualifies as prior art or that this document is material to patentability of the present application or that a search has been made.

Since the present Application was filed after June 30, 2003, a copy of any U.S. Patent and any U.S. Patent Application Publication cited on the attached PTO Form 1449 is not being submitted with this Information Disclosure Statement pursuant to the July 11, 2003 waiver of 37 C.F.R. S 1.98(a)(2)(i) by the U.S. Patent and Trademark Office. However, copies of articles are being furnished.

Respectfully submitted,
Attorney for Applicant



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Date: December 15, 2003

FORM PTO-1449
(REV. 7-80)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

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TI-36749

LIST OF DOCUMENTS CITED BY APPLICANT
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APPLICANT

Christopher L. Kelley

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GROUP

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U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE (IF APPROPRIATE)
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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION Yes No
	BA						
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	BD						
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	CA	"Applied Centura DPS Etch - DPS Plus for Metal Applications", website http://www.appliedmaterials.com/products/metal_etch_dps_plus_centura.html , printed on 12/4/2003, 1 page.
	CB	"Applied Centura DPS Etch - DPS II for Metal Applications", website http://www.appliedmaterials.com/products/metal_etch_dps_ii_centura_300.html , printed on 12/4/2003, 1 page.
	CC	"Applied Centura DPS Etch - DPS Plus for Silicon Applications", website http://www.appliedmaterials.com/products/silicon_etch_dps_plus.html , printed on 12/4/2003, 1 page.
	CD	"Applied Centura DPS Etch - DPS II for Silicon Applications", website http://www.appliedmaterials.com/products/silicon_etch_dps_ii_300.html , printed on 12/4/2003, 1 page.
	CE	"Applied Centura eMAX Etch", website http://www.appliedmaterials.com/products/dielectric_etch_emax.html , printed on 12/4/2003, 1 page.

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CA	"Applied Centura EnTek Etch - for Dielectric Applications", website http://www.appliedmaterials.com/products/dielectric_etch_emark_entek.html , printed on 12/4/2003, 1 page.
CC	"Applied Producer Etch", website http://www.appliedmaterials.com/products/producer_etch.html , printed on 12/04/2003, 1 page.
CD	"Applied Centura HART Etch for Silicon Applications", website http://www.appliedmaterials.com/products/silicon_etch_hart.html , printed on 12/4/2003, 1 page.
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